

Title (en)

BAFFLE DEVICE FOR HOT-DIP PLATING PROCESS

Title (de)

PRALLBLECHVORRICHTUNG FÜR SCHMELZTAUCHBESCHICHTUNGSVERFAHREN

Title (fr)

DISPOSITIF DÉFLECTEUR POUR PROCÉDÉ DE PLACAGE PAR IMMERSION À CHAUD

Publication

**EP 4372120 A4 20240522 (EN)**

Application

**EP 22921011 A 20221207**

Priority

- KR 20220128301 A 20221007
- KR 2022019759 W 20221207

Abstract (en)

[origin: WO2024075896A1] The present invention relates to a baffle device for a hot-dip plating process. The baffle device comprises a baffle plate and a support for supporting the baffle plate from above. The support includes an upper support provided with a first insertion groove, a second insertion groove, and a first fixing member. Also, the support further includes a lower support provided with a first roller, a second roller, and a second fixing member. In order to couple the upper support and the lower support, the first roller and the second roller are inserted into the first insertion groove and the second insertion groove. When the first roller and the second roller are inserted into the first insertion groove and the second insertion groove, the first fixing member and the second fixing member come into close contact with each other and suppress the movement of the lower support relative to the upper support.

IPC 8 full level

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CPC (source: EP)

**C23C 2/003** (2013.01); **C23C 2/16** (2013.01); **C23C 2/20** (2013.01)

Citation (search report)

- [XAYI] KR 100613893 B1 20060822
- [YA] KR 101008184 B1 20110114 - SAM WOO [KR]
- See also references of WO 2024075896A1

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DOCDB simple family (publication)

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